

Notice of References Cited

Application/Control No.

09/866,843

Applicant(s)/Patent Under
Reexamination
OGURE ET AL.

Examiner

George A. Goudreau

Art Unit

1763

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	V	"Neutral-Beam-Assisted Etching of Silicon Dioxide-a Charge Free Etching Process"; □□Japanese Journal of Applied Physics; Part 1: Regular Papers, Short Notes & Review Papers (1990'); 29(10); Mizutani et. al.; abstract only
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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